

# TCAD simulations of innovative Low-Gain Avalanche Diodes for particle detector design and optimization

F. Moscatelli

On behalf of CNR-IOM, INFN and University of Perugia (Italy) and INFN and University of Torino (Italy) groups



This work has been supported by the Italian PRIN MIUR 2017 "4DInSiDe" research project and by the European Union's Horizon 2020 Research and Innovation programme under Grant Agreement No 101004761, AIDAinnova project.







## Outline

- Motivations
- TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD LGAD





### Outline

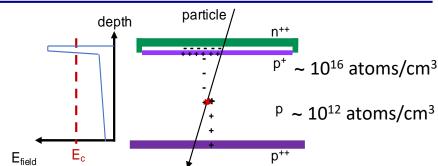
- Motivations
- > TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- ➤ Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD





#### **Motivations**

✓ **LGADs** are **n-in-p silicon** sensors Operated in **low-gain regime** (20 – 30) **Critical electric field** ~ **20** – **30** V/µm



- ✓ The acceptor removal mechanism<sup>[1]</sup> deactivates the p<sup>+</sup>-doping of the gain layer with irradiation
- ✓ **Device-level simulation tools**<sup>[2]</sup> **for predicting** the electrical behaviour and the charge collection properties **up to the highest particle fluences**.
- ✓ Implementation of a proper radiation damage model within the simulation environment.
- [1] [M. Ferrero et al., doi:10.1016/j.nima.2018.11.121]

[2] Synopsys© Sentaurus TCAD





## Outline

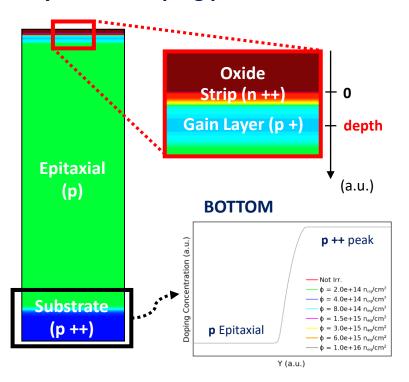
- Motivations
- > TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- ➤ Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD

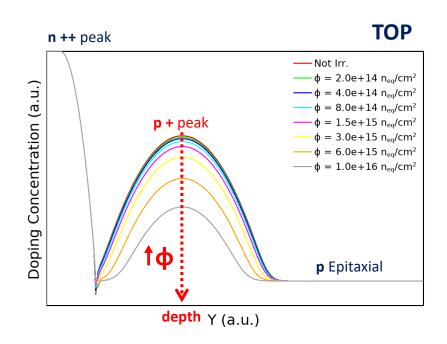




## TCAD simulation of LGAD devices (1/2)

√ Layout and doping profile





Gaussian Gain Layer profile





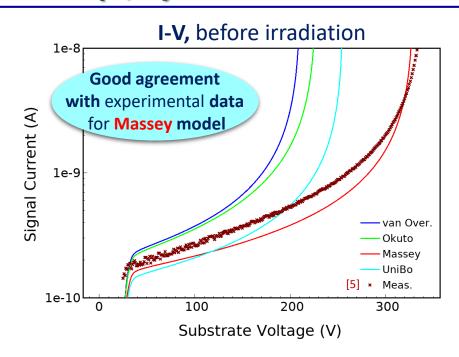
## TCAD simulation of LGAD devices (2/2)

- ✓ Physical models
- √ Generation/Recombination rate
  - Shockley-Read-Hall, Band-To-Band Tunneling, Auger
  - Avalanche Generation => impact ionization models, such as van Overstraeten-de Man, Okuto-Crowell, Massey<sup>[2]</sup>, UniBo
- √ Fermi-Dirac statistics
- ✓ **Carriers mobility variation** doping and field dependent
- ✓ Physical parameters
  - e-/h+ recombination lifetime
- ✓ Radiation damage models
- √ "New University of Perugia model"
  - Combined surface and bulk TCAD damage modelling scheme<sup>[3]</sup>
  - Traps generation mechanism
- $\checkmark$  Acceptor removal mechanism  $\Rightarrow$   $N_{GL}(\phi) = N_A(\mathbf{0})e^{-c\phi}$  where
  - Gain Layer (GL)
  - c, removal rate, evaluated using the Torino parameterization<sup>[4]</sup>

[2] M. Mandurrino et al., Numerical Simulation of Charge Multiplication in Ultra-Fast Silicon Detectors (UFSD) and Comparison with Experimental Data, IEEE, 2017.

[3] AIDA2020 report, TCAD radiation damage model - CERN Document Server.

[4] M. Ferrero et al., *Radiation resistant LGAD design*, Nucl. Inst. And Meth. In Phys. Res. A, November 30, 2018.



Temperature **300 K.** Electrical contact area **1mm**<sup>2</sup>

[5] V. Sola et al., First FBK production of 50 μm ultra-fast silicon detectors, Nucl. Instrum. Methods Phys. Res. A, 2019.





## Outline

- Motivations
- TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- ➤ Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD

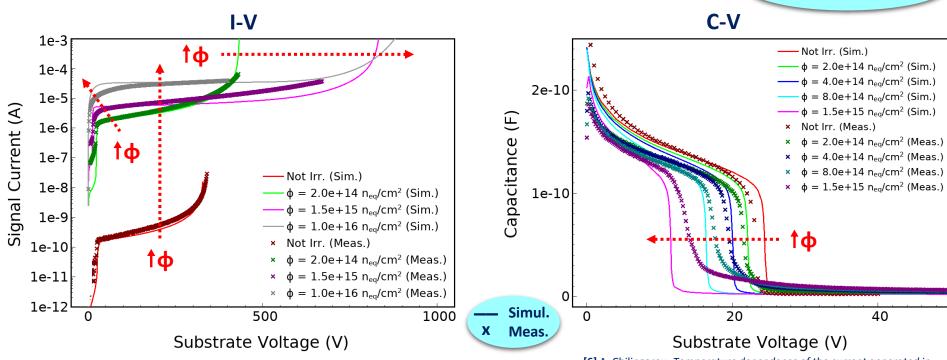




# Static (DC) and small-signal (AC) behavior

#### ✓ Comparison with experimental data, before and after irradiation

#### **Good agreement!**



Avalanche model: Massey. Frequency 1 kHz for C-Vs. Electrical contact area 1mm<sup>2</sup>

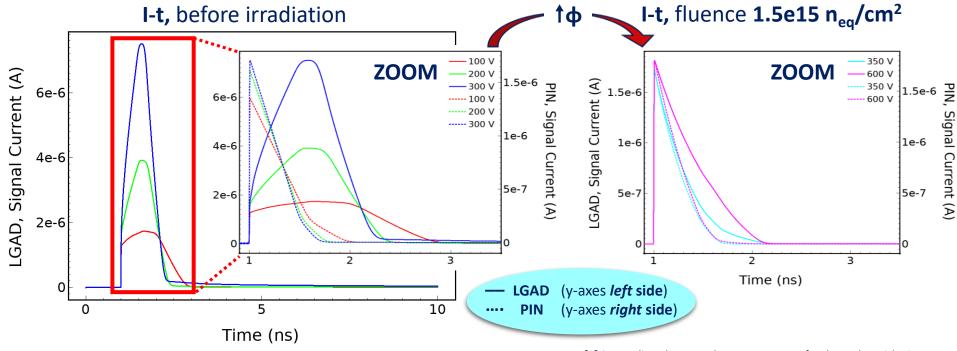






## Transient response

✓ Comparison between LGAD and PIN response to the MIP for different V<sub>bias</sub>





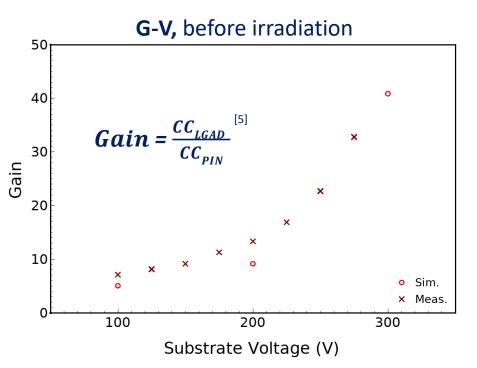
[7] S. Meroli et al., Energy loss measurement for charged particles in very thin silicon layers, JINST 6 P06013, 2011.



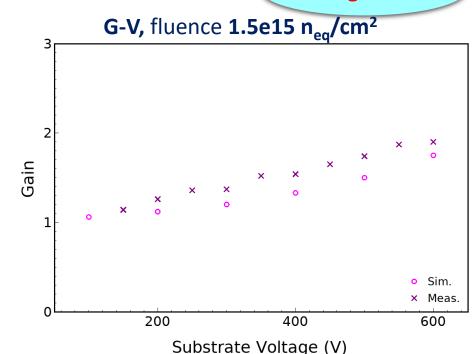
Avalanche model: Massey. Temperature 300 K. Electrical contact area 1mm<sup>2</sup>

#### Gain calculation





**Good agreement!** 



[5] V. Sola et al., First FBK production of 50 μm ultra-fast silicon detectors, Nucl. Instrum. Methods Phys. Res. A, 2019.

Avalanche model: Massey. Temperature 300 K. Electrical contact area 1mm<sup>2</sup>



## Outline

- Motivations
- > TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- ➤ Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD





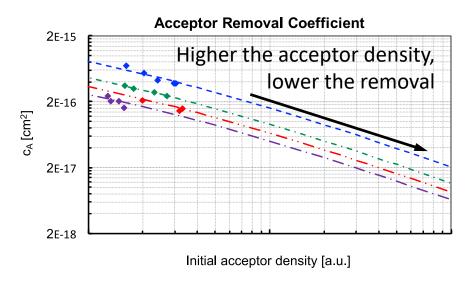
#### LGAD for extreme fluences

- ✓ Difficult to operate silicon sensors above  $10^{16}$  n<sub>ea</sub>/cm<sup>2</sup> due to:
- defects in the silicon lattice structure → increase of the dark current
- trapping of the charge carriers  $\longrightarrow$  decrease of the charge collection efficiency
- change in the bulk effective doping  $\rightarrow$  impossible to fully deplete the sensors
- For LGAD acceptor removal mechanism
- ✓ The options to overcome the present limits above  $10^{16}$  n<sub>eq</sub>/cm<sup>2</sup> are:
- 1. **saturation** of the radiation damage effects above 5·10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup>
- 2. the use of **thin** active substrates  $(20 40 \mu m)$
- 3. extension of the charge carrier multiplication up to  $10^{17}$   $n_{eq}/cm^2$





## Towards a Radiation Resistance Design

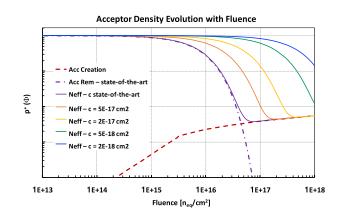


The acceptor removal mechanism deactivates the p\*-doping of the gain layer with irradiation according to

$$p_{+}(\Phi) = b_{+}(0) \cdot e_{-c \forall \Phi}$$

where  $c_A$  is the acceptor removal coefficient  $c_A$  depends on the initial acceptor density,  $p^+(0)$ , and on the defect engineering of the gain layer atoms

Lowering c<sub>A</sub> extends the gain layer survival up to the highest fluences







## Compensation

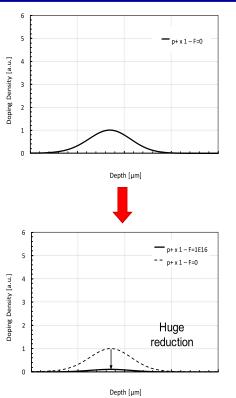
Impossible to reach the design target with the present design of the gain layer

Use the interplay between acceptor and donor removal to keep a constant gain layer active doping density

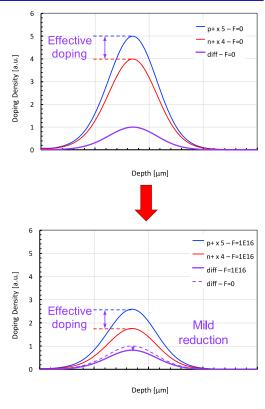
Many unknown:

- ightharpoonup donor removal coefficient, from  $n^+(\Phi) = n^+(0) \cdot e^{-cD\Phi}$
- ightharpoonup interplay between donor and acceptor removal ( $c_D$  vs  $c_A$ )
- effects of substrate impurities on the removal coefficients

V. Sola et al, "A compensated design of the LGAD gain layer», NIMA 1040 (2022) 167232







Compensated LGAD





## Compensation – doping evolution with fluence

Three scenarios of net doping evolution with fluence are possible, according to the acceptor and donor removal interplay:

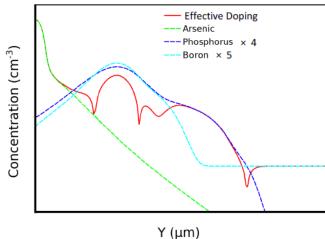
- 1.  $c_A \sim c_D$ 
  - $p^+$  &  $n^+$  difference will remain constant  $\Rightarrow$  unchanged gain with irradiation
  - → This is the best possible outcome
- 2.  $c_A > c_D$ 
  - effective doping disappearance is slower than in the standard design
  - → Co-implantation of Carbon atoms mitigates the removal of p\*-doping
- 3.  $c_A < c_D$ 
  - $n^+$ -atoms removal is faster  $\Rightarrow$  increase of the gain with irradiation
  - → Co-implantation of Oxygen atoms might mitigate the removal of n<sup>+</sup>-doping



## Compensation - simulation

Process simulations of Boron (p<sup>+</sup>) and Phosphorus (n<sup>+</sup>) implantation and activation reveal the different shape of the two profiles (TCAD Silvaco)

#### **Doping Profiles from Process Simulation**



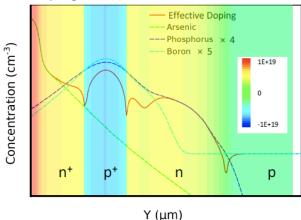




## Compensation - simulation

Process simulations of Boron (p<sup>+</sup>) and Phosphorus (n<sup>+</sup>) implantation and activation reveal the different shape of the two profiles (TCAD Silvaco)

Doping Profiles from Process Simulation



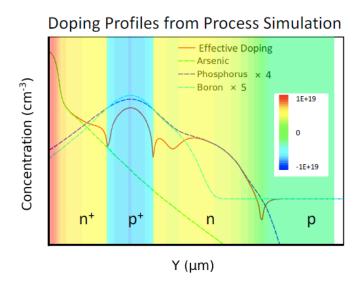
Difficult to precisely control the interplay between the implanted p<sup>+</sup> and n<sup>+</sup> densities

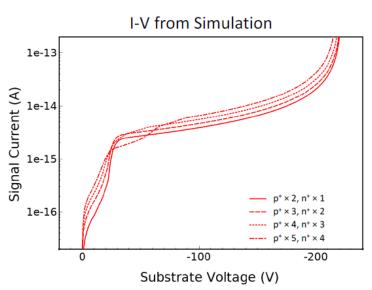




## Compensation - simulation

Process simulations of Boron (p<sup>+</sup>) and Phosphorus (n<sup>+</sup>) implantation and activation reveal the different shape of the two profiles (TCAD Silvaco)





→ The simulation of the electrostatic behaviour show that it is possible to reach similar multiplication for different values of initial compensation (TCAD Synopsys)





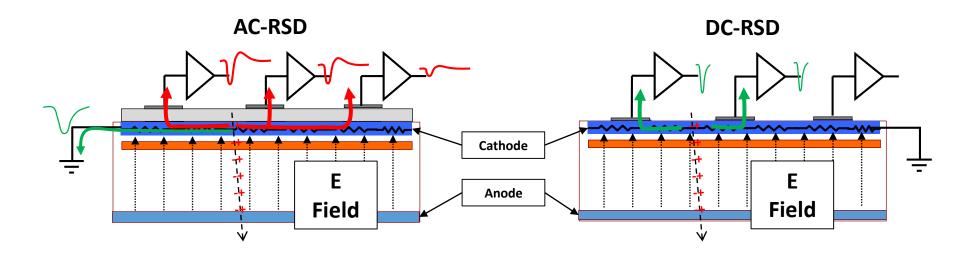
## Outline

- Motivations
- > TCAD simulation of LGAD devices
  - ☐ Layout and doping profile
  - Physical models and parameters
- ➤ Methodology (DC, AC and transient response)
- Application of the developed model
  - Compensated LGAD
  - RSD





#### RSD and DC-RSD



This design has been manufactured in several productions by FBK, BNL, and HPK

This design is presently under development by FBK

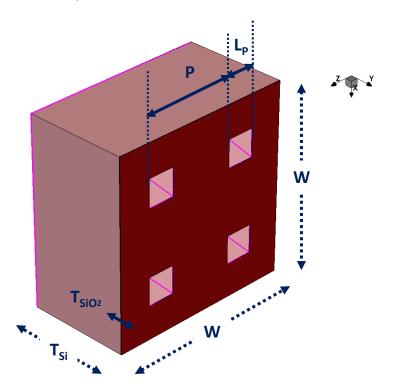
The main advantage of the DC-RSD design is to limit the signal spread





## Simulated layout

√ 3D structure, 2x2 PADs



#### √ Silicon (Si)

Width (W)100 μm

Thickness (T)55 μm

#### √ Silicon Oxide (SiO₂)

Width (W) 100 μm

Pad Length (L<sub>P</sub>)

15 µm

o Pitch (P)

50 µm

Thickness (T)

0,30 µm



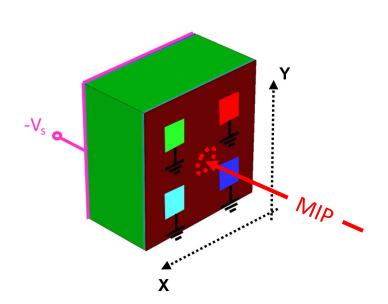


# Active (TV) behavior (1/2)

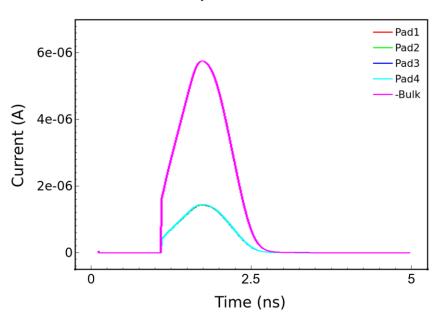
✓ 3D structure, 2x2 PADs

 $@ R_{s,n++} \approx 203 \Omega_{sq}$ 

- hit 1 (center hit), 1 MIP
- $\circ$  V<sub>s</sub> = -200 V



**I-t,** not irr.





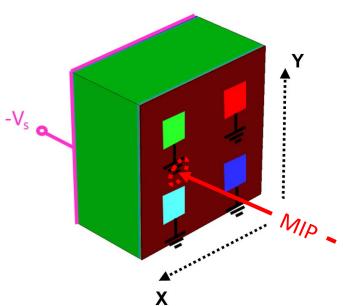


# Active (TV) behavior (2/2)

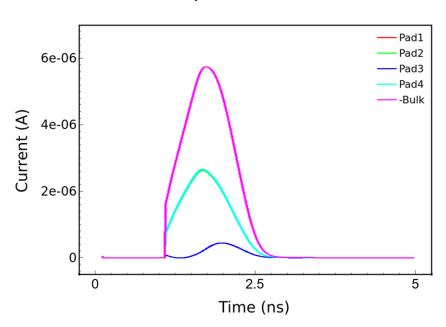
✓ 3D structure, 2x2 PADs

@  $R_{s,n++} \approx 203 \Omega_{sq}$ 

- o hit 2, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V



I-t, not irr.

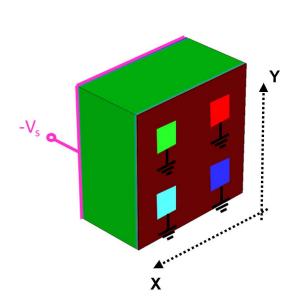




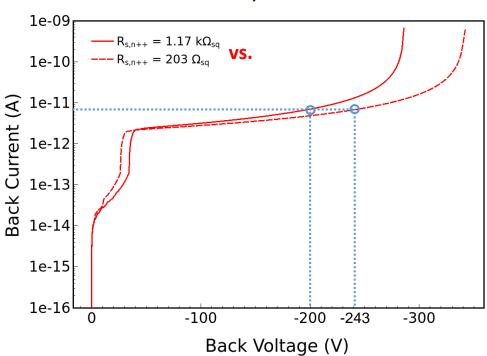


## Different n<sup>++</sup> layer resistance

✓ 3D structure, 2x2 PADs => LGAD



I-V, not irr.



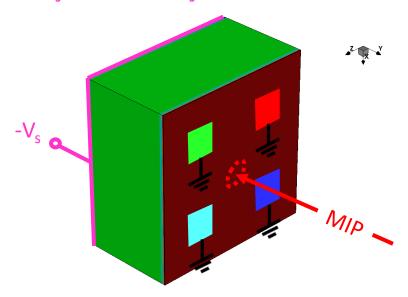




## Different n<sup>++</sup> layer resistance: Active behavior

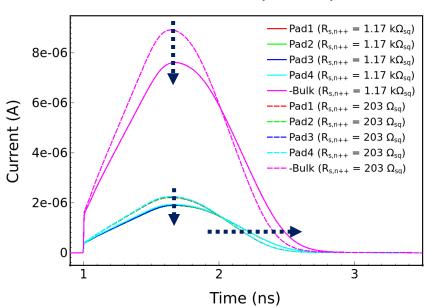
- √ 3D structure, 2x2 PADs => LGAD
  - hit 1 (center hit), 1 MIP

$$V_s = -243 \text{ V} ---> V_s = -200 \text{ V}$$



$$R_{s,n++} \approx 203 \Omega_{sq} \longrightarrow R_{s,n++} \approx 1,17 k\Omega_{sq}$$

I-t, not irr. (ZOOM)

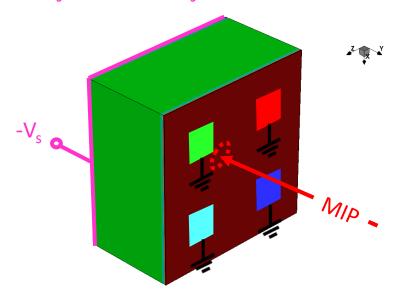






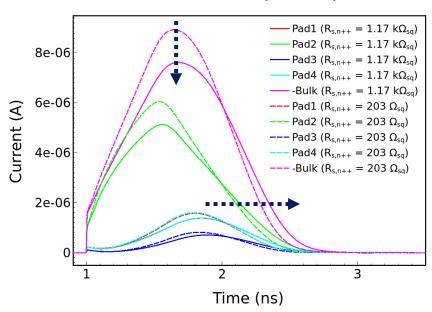
# Different n<sup>++</sup> layer resistance: Active (TV) behavior

- ✓ 3D structure, 2x2 PADs => LGAD
  - hit 3, 1 MIP
  - $\circ$  V<sub>s</sub> = -243 V ---> V<sub>s</sub> = -200 V



$$R_{s,n++} \approx 203 \Omega_{sq} \longrightarrow R_{s,n++} \approx 1,17 k\Omega_{sq}$$

I-t, not irr. (ZOOM)

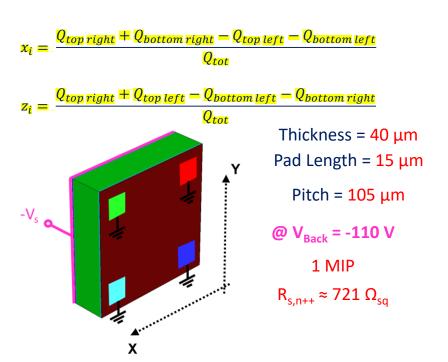


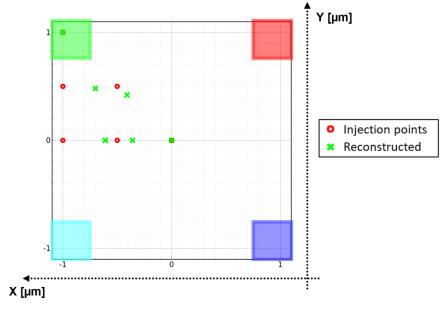




## Reconstruction (1/2)

✓ The position is reconstructed using the CHARGE imbalance

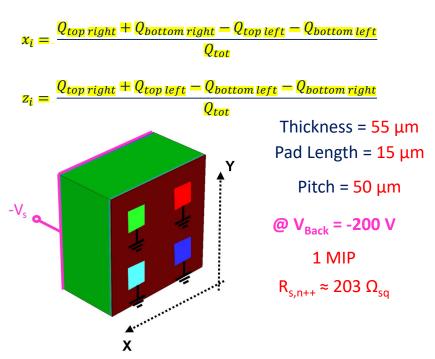


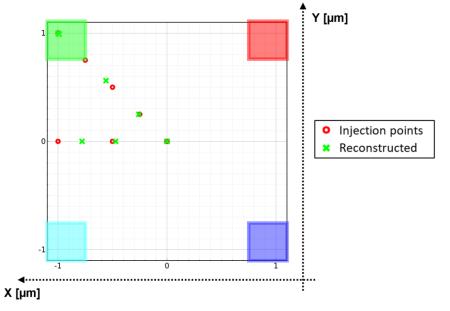


**Results** from *TCAD* simulations

## Reconstruction (2/2)

✓ The position is reconstructed using the CHARGE imbalance





**Results** from *TCAD* simulations

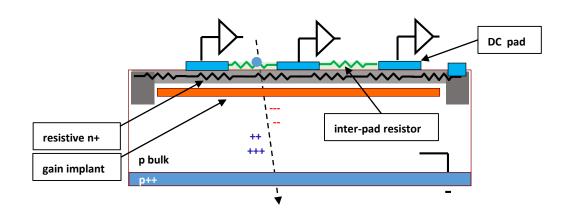




#### DC-RSD with resistors

The DC-RSD design can also be done **including resistors** between the read-out electrodes.

these resistors could improve the position resolution of the sensors



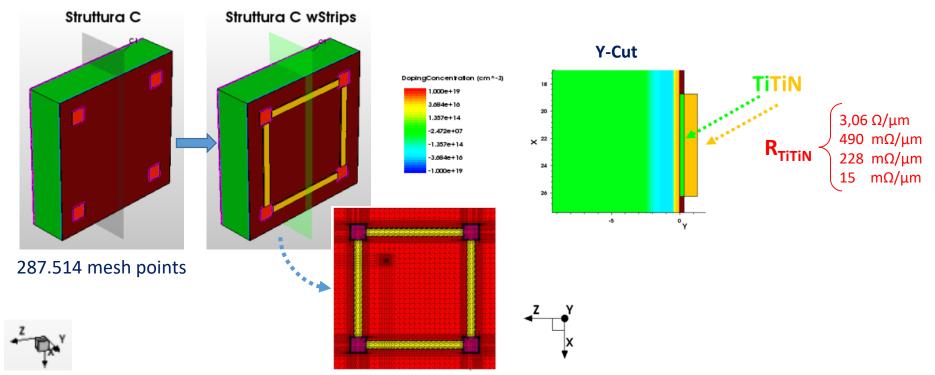




#### RSD with resistors between read-out electrodes

✓ 3D structure, 2x2 PADs => LGAD

@  $R_{s,n++} \approx 721 \Omega_{sq}$ 





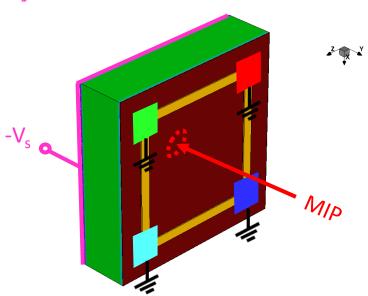


# Active (TV) behavior (1/2)

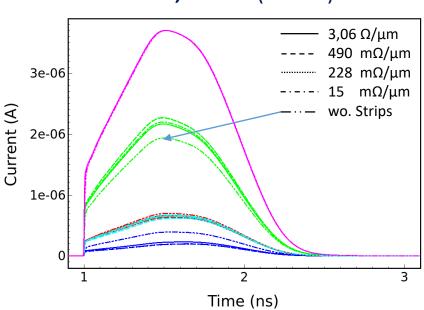
✓ 3D structure, 2x2 PADs, type C w Strip

@  $R_{s,n++} \approx 721 \Omega_{sq}$ 

- o hit 3, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V



#### I-t, not irr. (ZOOM)





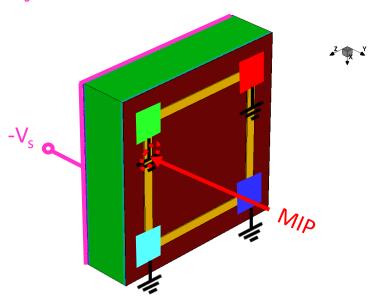


# Active (TV) behavior (2/2)

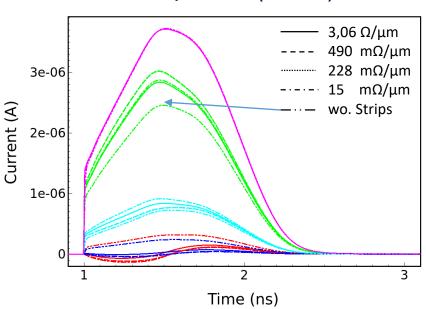
✓ 3D structure, 2x2 PADs, type C w Strip

 $@ R_{s,n++} \approx 721 \Omega_{sq}$ 

- o hit 8, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V



#### I-t, not irr. (ZOOM)

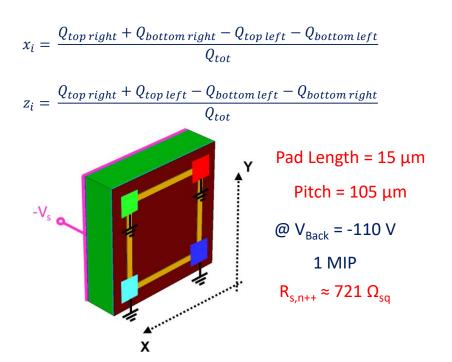


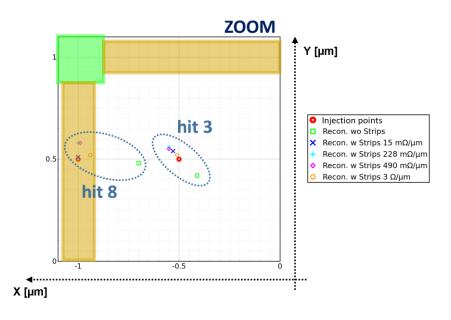




## Reconstruction with strips

✓ The position is reconstructed using the CHARGE imbalance





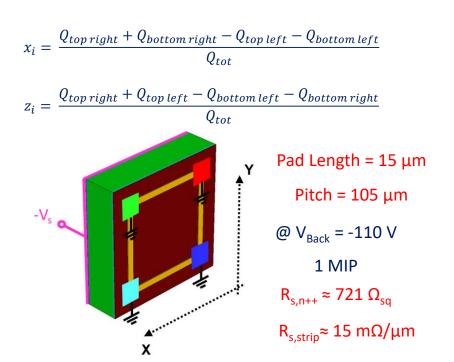
**Results** from *TCAD* simulations

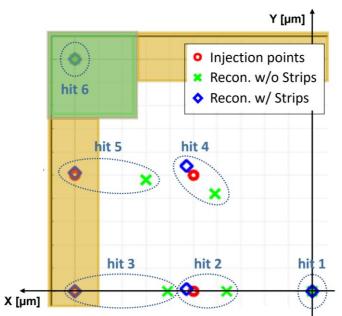




## Reconstruction with strips

✓ The position is reconstructed using the CHARGE imbalance





**Results** from *TCAD* simulations

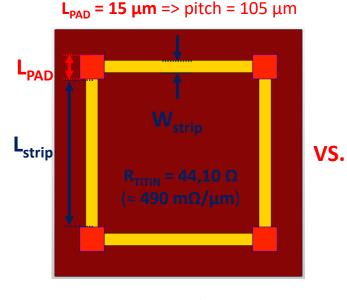




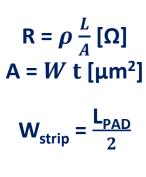
## Impact of the pad size

✓ 3D structure, 2x2 PADs => LGAD

 $\mathbf{@}\ \mathsf{R}_{\mathsf{s,n++}} \approx 721\ \Omega_{\mathsf{sq}}$ 



 $L_{PAD} = 7 \ \mu m \Rightarrow pitch = 109 \ \mu m$   $R_{Ti} = 53,56 \ \Omega$   $R_{TiN} = 714 \ \Omega$  V  $R_{TiTiN} = 49,82 \ \Omega$   $(\approx 488 \ m\Omega/\mu m)$ 



hit 3

351.889 mesh points

hit 8

350.489 mesh points

273.829 mesh points

275.654 mesh points

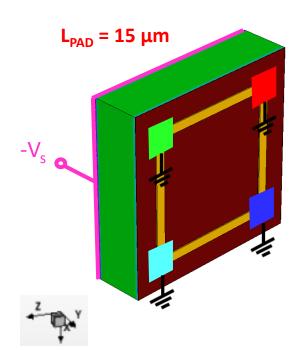


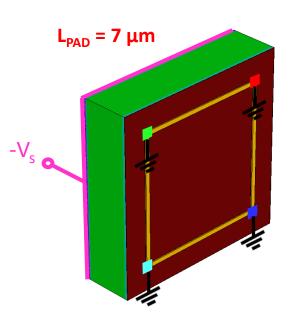


# Simulated setup

✓ Electric contacts and circuit

## C w Strips





- $\square$  BACK =>  $V_s$  = -110 V
- $\Box$  **PAD1** =>  $V_1 = 0$  (**GND**)
- $\square$  **PAD2** =>  $V_2 = 0$  (**GND**)
- $\square$  **PAD3** =>  $V_3 = 0$  (**GND**)
- $\square$  **PAD4** =>  $V_4 = 0$  (**GND**)

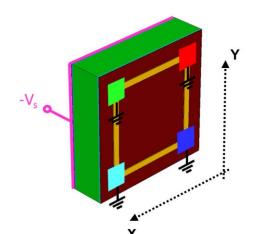


# Reconstruction (1/2)

## ✓ The position is reconstructed using the CHARGE imbalance

$$x_i = \frac{Q_{top\,right} + Q_{bottom\,right} - Q_{top\,left} - Q_{bottom\,left}}{Q_{tot}}$$

$$z_i = \frac{Q_{top\,right} + Q_{top\,left} - Q_{bottom\,left} - Q_{bottom\,right}}{Q_{tot}}$$



## Pad Length = 15 μm

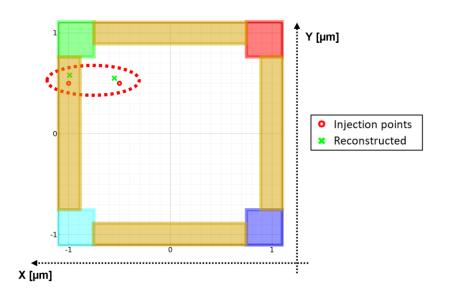
Pitch = 
$$105 \mu m$$

@ 
$$V_{Back} = -110 V$$

1 MIP

$$R_{s,n++} \approx 721 \Omega_{sq}$$

 $R_{TITIN} \approx 490 \text{ m}\Omega/\mu\text{m}$ 



**Results** from *TCAD* simulations





# Reconstruction (2/2)

## ✓ The position is reconstructed using the **CHARGE imbalance**

$$x_i = \frac{Q_{top\,right} + Q_{bottom\,right} - Q_{top\,left} - Q_{bottom\,left}}{Q_{tot}}$$

$$z_i = \frac{Q_{top\,right} + Q_{top\,left} - Q_{bottom\,left} - Q_{bottom\,right}}{Q_{tot}}$$

$$Pad \, Length = 7 \, \mu m$$

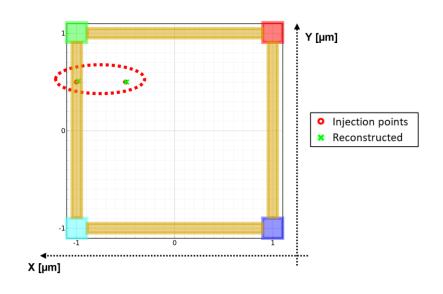
$$Pitch = 109 \, \mu m$$

$$@ \, V_{Back} = -110 \, V$$

$$1 \, MIP$$

$$R_{s,n++} \approx 721 \, \Omega_{sq}$$

$$R_{TITIN} \approx 488 \, m\Omega/\mu m$$



**Results** from *TCAD* simulations





## Conclusions

- ✓ Strategy for TCAD numerical simulation of LGAD devices.
- ✓ Results obtained under different operating conditions (device biasing, fluence).
- ✓ Good agreement between simulation predictions and experimental data for both non-irradiated and irradiated LGAD device.
- ✓ **Combination** of "New University of Perugia TCAD model" and the "acceptor removal" analytical model is used to simulate the **radiation damage effects** 
  - => successful description of the decrease in gain with an increase in fluence.
- ✓ **Application** of the validated simulation framework for the analysis of **different innovative options in particular Compensated and RSD LGAD=> optimization** for their **use in the future HEP experiments**.
- ✓ Ongoing comparison between simulation findings and new experimental data of real devices => new guidelines for future production of radiation-resistant LGADs.





# **BACKUP SLIDES**

# Low-Gain Avalanche Diodes (LGADs)

- Most promising devices to cope with the high spatial density of particles hits due to the increasing radiation fluence expected in the HL-LHC at CERN.
- ➤ **LGAD structure**: pin diode with the additional inclusion of a p+-type layer just below the n-contact, which is commonly called *multiplication layer*.
- > By applying a reverse-bias, this layer is responsible for a multiplication of carriers.

$$G_{\text{aval}} = \alpha_n n v_n + \alpha_p p v_p$$
 
$$\alpha = \frac{E}{E_{th}} e^{-\frac{E_i}{E}}$$

- ➤ By accurately chosing the **peak and shape of the implanted p+ profile**, it is possible to control the **avalanche mechanism** in order to obtain the required internal gain with a sufficiently high breakdown voltage.
- > One of the best tools for predicting the behaviour of the avalanche process is device-level simulation









# Technology-CAD simulations

- > TCAD simulation tools solve fundamental, physical partial differential equations, such as diffusion and transport equation for discretized geometries (finite element meshing).
- > This deep physical approach gives TCAD simulation **predictive accuracy**.
- Synopsys© Sentaurus TCAD

$$\nabla \cdot (-\varepsilon_s \nabla \phi) = q \quad (N_D^+ - N_A^- + p - n)$$

$$\frac{\partial n}{\partial t} - \frac{1}{q} \nabla \cdot \vec{J}_n = U_n$$

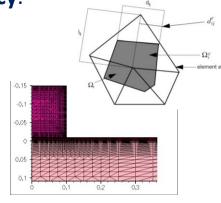
$$\frac{\partial p}{\partial t} + \frac{1}{q} \nabla \cdot \vec{J}_p = U_p$$

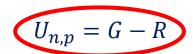
 $\vec{J}_n, \vec{J}_p$ 



Electron continuity

Hole continuity





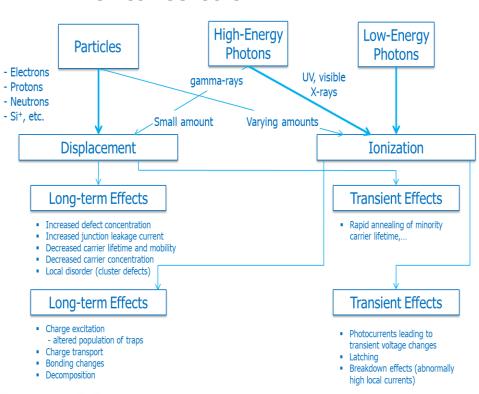






# Radiation damage effects (1/2)

## √ in silicon sensors



Two main **types of radiation damage** in detectors materials:

- > SURFACE damage => Ionization
  - ✓ Build-up of trapped charge within the oxide;
  - ✓ Bulk oxide traps increase;
  - ✓ Interface traps increase;
  - $\checkmark$  Q<sub>ox</sub>, N<sub>IT</sub>.
- BULK damage => Atomic displacement
  - ✓ Silicon lattice defect generations;
  - ✓ Point and cluster defects;
  - ✓ Deep-level trap states increase;
  - ✓ Change of effective doping concentration;
  - ✓ N<sub>T</sub>.







# Radiation damage effects (2/2)

## √ in LGAD devices

- ➤ Acceptor removal mechanism<sup>[1]</sup>: the active (substitutionals) doping elements are partially removed from their lattice sites due to the ionizing radiation and then de-activated after a kick-out reaction (Watkins mechanism<sup>[2]</sup>) that produces ion-acceptor complexes (interstitials)
- > Transformation of electrically active acceptors into defect complexes that no longer have dopant properties
- > This has been recently suggested as a possible explanation for the significant degradation of gain (charge multiplication) observed on LGAD devices after irradiation.

<sup>[2]</sup> G. D. Watkins, Defects and Their Structure in Non-metallic Solids, B. Henderson and A. E. Hughes, Eds. New York: Plenum, 1975







<sup>[1]</sup> G. Kramberger, M. Baselga et al., J. Inst., vol. 10, no. 7, p. P07006, 2015

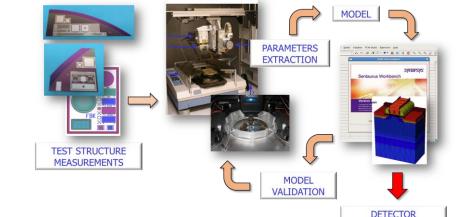
# TCAD radiation damage models used

- "New University of Perugia model"
  - ✓ Combined surface and bulk TCAD damage modelling scheme<sup>[3]</sup>
  - ✓ Traps generation mechanism
- Acceptor removal mechanism

$$N_{GL}(\phi) = NA(0)e^{-c\phi}$$

## where

- Gain Layer (GL)
- c, removal rate, evaluated using the
   Torino parameterization<sup>[4]</sup>



## Surface damage (+ Q<sub>ox</sub>)

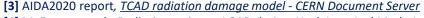
Туре	Energy (eV)	Band width (eV)	Conc. (cm <sup>-2</sup> )
Acceptor	$E_C \le E_T \le E_{C}$ -0.56	0.56	$D_{IT} = D_{IT}(\Phi)$
Donor	$E_V \le E_T \le E_V + 0.6$	0.60	$D_{IT} = D_{IT}(\Phi)$

#### **Bulk** damage

Type	Energy (eV)	η (cm <sup>-1</sup> )	σ <sub>n</sub> (cm²)	σ <sub>h</sub> (cm²)
Donor	E <sub>C</sub> - 0.23	0.006	2.3×10 <sup>-14</sup>	2.3×10 <sup>-15</sup>
Acceptor	E <sub>C</sub> - 0.42	1.6	1×10 <sup>-15</sup>	1×10 <sup>-14</sup>
Acceptor	E <sub>C</sub> - 0.46	0.9	7×10 <sup>-14</sup>	7×10 <sup>-13</sup>

**OPTIMIZATION** 

CCE, I-V, C-V, ..



<sup>[4]</sup> M. Ferrero et al., *Radiation resistant LGAD design*, Nucl. Inst. And Meth. In Phys. Res. A, November 30, 2018.







# Methodology





## DC / AC analysis



## **Transient analysis**



## Gain calculation

## DC biasing (static)

- o n cathode: 0 V
- o p anode: sweep
  - ✓ start = 0 V
  - √ step = 25 V (from 100 V)
  - ✓ stop = 1000 V
- Temperature
  - ✓ 300 K for not irr., 253 K for irr. [7]

## AC biasing (small-signal)

- For each DC bias step, superimposition of a 1 V<sub>pp</sub>, 1 kHz sinusoid
- Impedance matrix for each node of the discretized grid
- o Temperature 300 K for not irr. / irr.

- For each DC bias step, one
   Time-Variant (TV) simulation of
   impinging particle (MIP),
   following the "Heavylon" model
- instant of penetration 1 ns
- through the whole device
- Linear Energy Transfer (LET)

$$LET_f = \frac{E_{LOSS}}{E} \quad \frac{pC}{\mu m}$$

where

$$E = 3,68 \ eV$$

[5] 
$$\mathbf{E}_{LOSS} = 0.027 \log(\mathbf{y}) + 0.126 \frac{ke^{-1}}{\mu m}$$

- Leakage current calculation
   instant = 0,9 ns
- Leakage current offset subtracted from the simulated I(t) curve
- Calculation of Collected Charge
   (CC) as the integral of the current

$$Gain = \frac{CC_{LGAD}}{CC_{PIN}}$$

[6]

[5] S. Meroli et al., Energy loss measurement for charged particles in very thin silicon layers, JINST 6 P06013, 2011

 $\textbf{[6] V. Sola et al., } \textit{First FBK production of 50} \ \mu \textit{m ultra-fast silicon detectors,} \ \textit{Nucl. Instrum.} \ \textit{Methods Phys. Res. A, 2019}$ 

[7] A. Chilingarov, *Temperature dependence of the current generated in si bulk*, JINST 8 P10003, 2013.



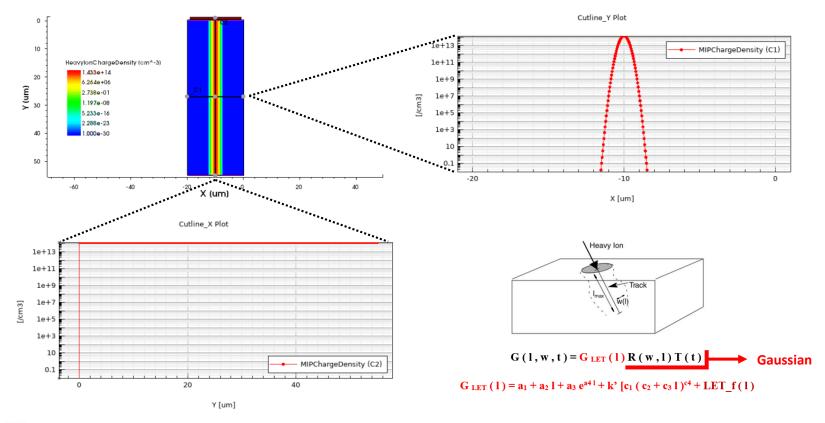








# Transient responce: "HeavyIon" model







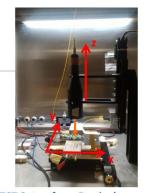


INFN

## Pre-Irradiation: Experimental Data (FBK UFSD2 Production)

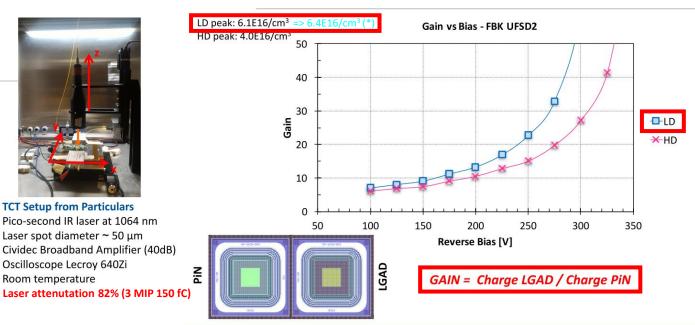






**TCT Setup from Particulars** 

Pico-second IR laser at 1064 nm Laser spot diameter ~ 50 µm Cividec Broadband Amplifier (40dB) Oscilloscope Lecroy 640Zi Room temperature



	W1	W8
Bias [V]	Gain LD	Gain HD
100	7.1	6.1
125	8.1	6.9
150	9.1	7.4
175	11.2	9.1
200	13.3	10.5
225	16.9	12.8
250	22.7	15.1
275	32.8	19.8
300	61.8	27.2
325	248.8	41.3
350	-	82.3

(\*) values updated to the latest measurements - V. Sola, 20/10

V. Sola

SIMULATION PLAN









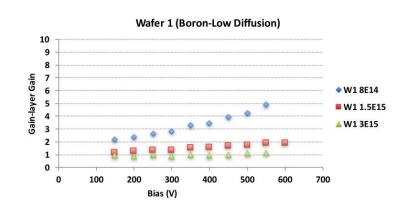
# Post-Irradiation: Experimental Data (FBK UFSD2 Production)







Pico-second IR laser at 1064 nm Laser spot diameter ~ 50 μm Cividec Broadband Amplifier (40dB) Oscilloscope Lecroy 640Zi Room temperature Laser attenutation 82% (3 MIP 150 fC)



GAIN = Charge LGAD / Charge PiN irradiated at the same fluence → gain from gain layer only

 $c_{1D} = 3.85E-16 \text{ cm}^2$ 

#### **W1**

Bias [V]	Gain		
	Ф=8Е14	Ф=1.5Е15	
150	2.1	1.14	
200	2.4	1.26	
250	2.7	1.36	
300	2.8	1.37	
350	3.3	1.52	
400	3.4	1.54	
450	3.9	1.65	
500	4.2	1.74	
550	4.9	1.87	
600	-	1.90	

V. Sola

SIMULATION PLAN

3

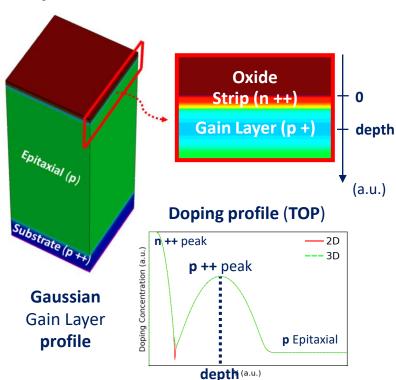


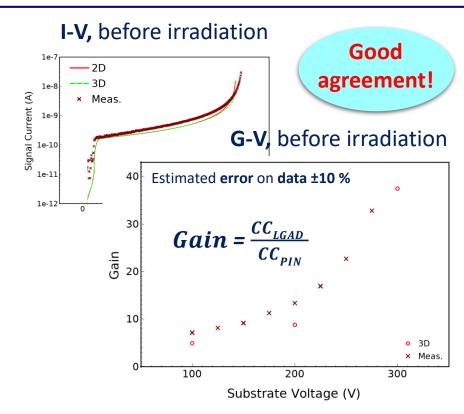




# Gain calculation (3D)







Avalanche model: Massey. Temp. 300 K. Electrical contact area 1mm<sup>2</sup>



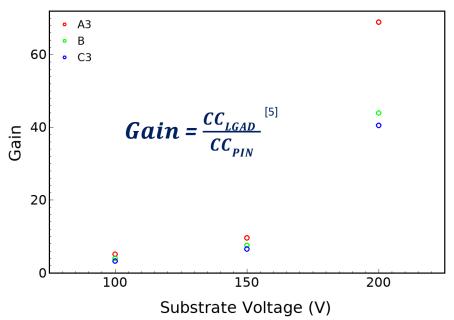




## Gain calculation

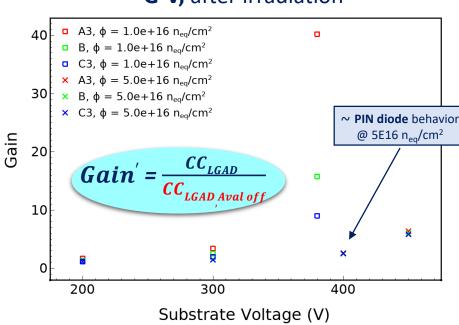
✓ Simulation results, before and after irradiation (fluences 1.0e16 and 5.0e16 n<sub>eq</sub>/cm²)

**G-V**, before irradiation



Avalanche model: Massey. Temperature 300 K

## **G-V**, after irradiation



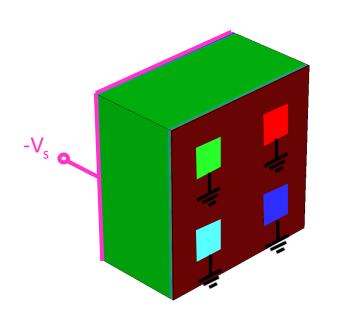
[5] V. Sola et al., First FBK production of  $50 \, \mu m$  ultra-fast silicon detectors, Nucl. Instrum. Methods Phys. Res. A, 2019.





# Simulated setup (2/2)

✓ Electric contacts and circuit

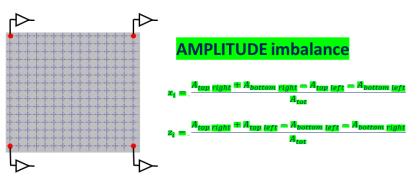


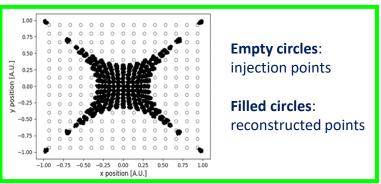


- **□ BACK** =>  $-V_s$ : 0 1000 V
- $\Box$  **PAD1** =>  $V_1 = 0$  (**GND**)
- $\square$  **PAD2** =>  $V_2 = 0$  (**GND**)
- $\square$  **PAD3** =>  $V_3 = 0$  (**GND**)
- $\square$  **PAD4** =>  $V_4 = 0$  (**GND**)

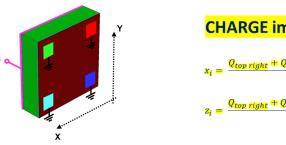
# Reconstruction (3/3)

## **Results** from *Spice* simulations



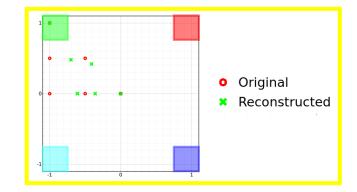


#### **Results** from *TCAD* simulations VS.



#### **CHARGE** imbalance

$$\begin{aligned} x_i &= \frac{Q_{top\ right} + Q_{bottom\ right} - Q_{top\ left} - Q_{bottom\ left}}{Q_{tot}} \\ z_i &= \frac{Q_{top\ right} + Q_{top\ left} - Q_{bottom\ left} - Q_{bottom\ right}}{Q_{ros}} \end{aligned}$$



From L. Menzio et al., 17th "TREDI" Workshop 03/03/22.



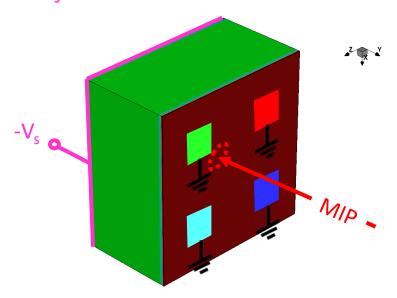


# Active (TV) behavior (3/7)

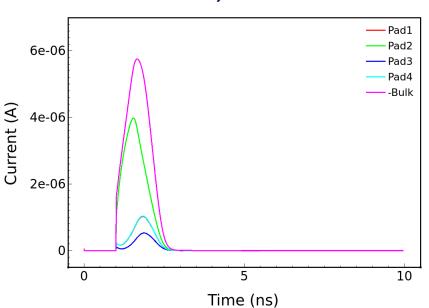
✓ 3D structure, 2x2 PADs

@  $R_{s,n++} \approx 203 \ \Omega_{sq}$ 

- o hit 3, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V







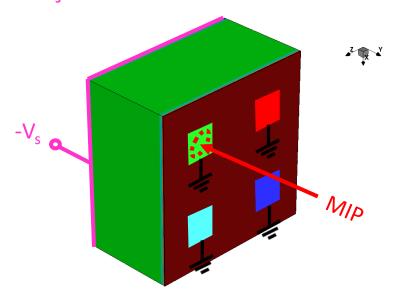
Avalanche model: Massey. Temperature 300 K

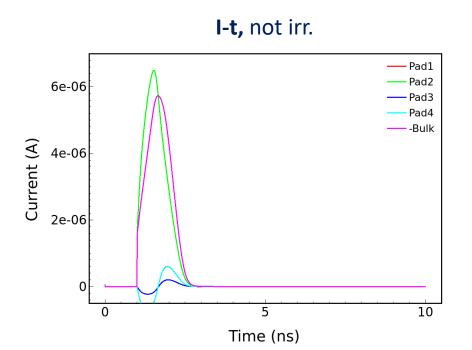
# Active (TV) behavior (4/7)

✓ 3D structure, 2x2 PADs

@ R<sub>s,n++</sub>  $\approx$  203  $\Omega_{sq}$ 

- o hit 4, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V



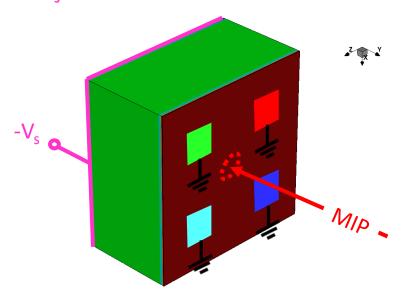


# Active (TV) behavior (5/7)

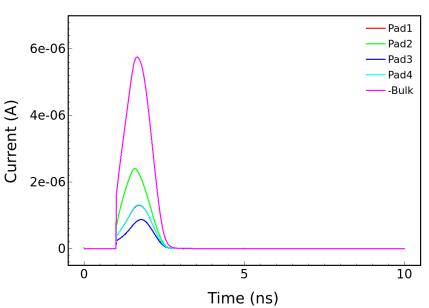
✓ 3D structure, 2x2 PADs

@  $R_{s,n++} \approx 203 \ \Omega_{sq}$ 

- o hit 5, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V







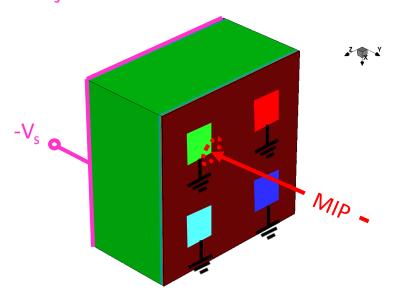
Avalanche model: Massey. Temperature 300 K

# Active (TV) behavior (6/7)

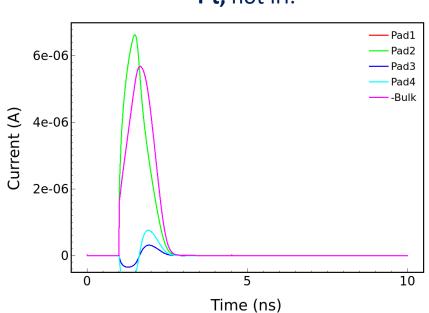
√ 3D structure, 2x2 PADs

@  $R_{s,n++} \approx 203 \Omega_{sq}$ 

- o hit 6, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V







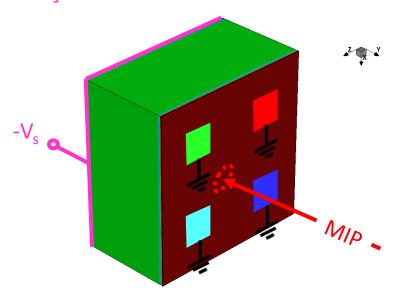
Avalanche model: Massey. Temperature 300 K

# Active (TV) behavior (7/7)

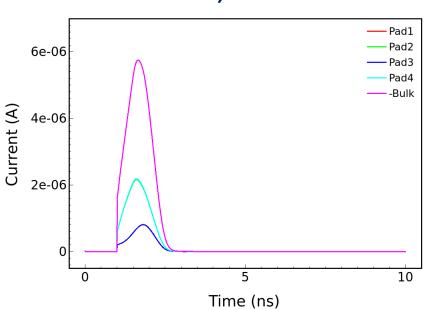
✓ 3D structure, 2x2 PADs

@ R<sub>s,n++</sub>  $\approx$  203  $\Omega_{sq}$ 

- o hit 7, 1 MIP
- $\circ$  V<sub>s</sub> = -200 V





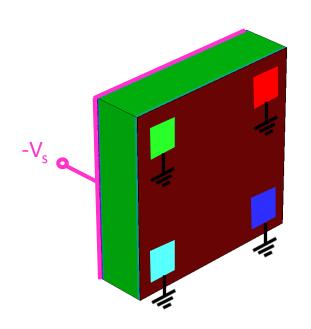


Avalanche model: Massey. Temperature 300 K

# **Next step** - Simulated setup

✓ Electric contacts and circuit

C





- $\square$  BACK =>  $V_s$  = -110 V
- $\Box$  **PAD1** =>  $V_1 = 0$  (**GND**)
- $\square$  **PAD2** =>  $V_2 = 0$  (**GND**)
- $\square$  **PAD3** =>  $V_3 = 0$  (**GND**)
- $\square$  **PAD4** =>  $V_4 = 0$  (**GND**)

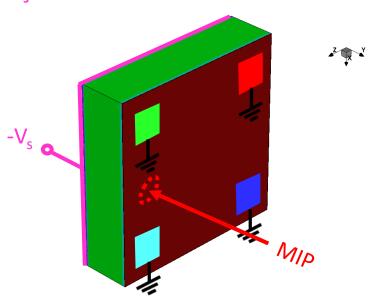
July 2020

# Active (TV) behavior (1/4)

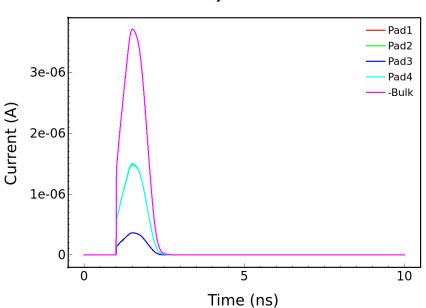
✓ 3D structure, 2x2 PADs, C wo Strip (19 h 06 min, 4 lic.)

@  $R_{s,n++} \approx 721 \Omega_{sq}$ 

- hit 2, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V



**I-t**, not irr.



Avalanche model: Massey. Temperature 300 K

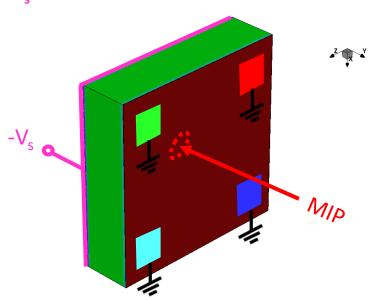
T. Croci et al., Perugia – May 11, 2022

# Active (TV) behavior (2/4)

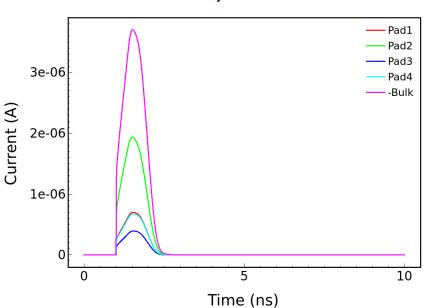
✓ 3D structure, 2x2 PADs, C wo Strip (19 h 21 min, 4 lic.)

@ R<sub>s,n++</sub>  $\approx$  721  $\Omega_{sq}$ 

- hit 3, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V



## I-t, not irr.



Avalanche model: Massey. Temperature 300 K

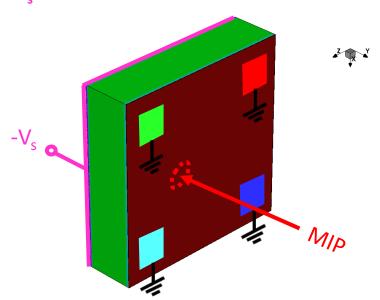
July 2020

# Active (TV) behavior (3/4)

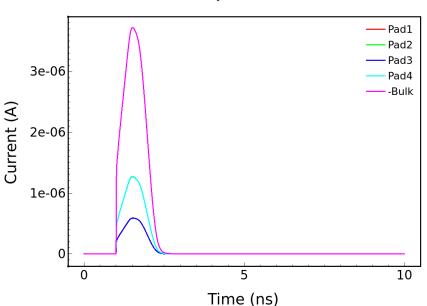
✓ 3D structure, 2x2 PADs, C wo Strip (19 h 20 min, 4 lic.)

@  $R_{s,n++} \approx 721 \Omega_{sq}$ 

- o hit 7, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V





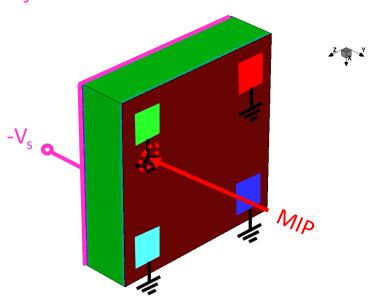


# Active (TV) behavior (4/4)

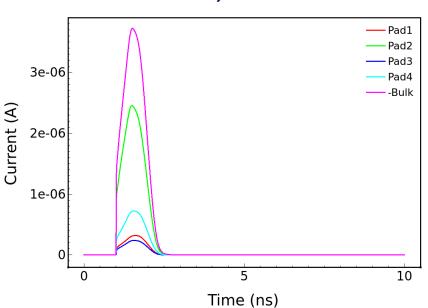
✓ 3D structure, 2x2 PADs, C wo Strip (18 h 42 min, 4 lic.)

@  $R_{s,n++} \approx 721 \Omega_{sq}$ 

- o hit 8, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V



I-t, not irr.



Avalanche model: Massey. Temperature 300 K

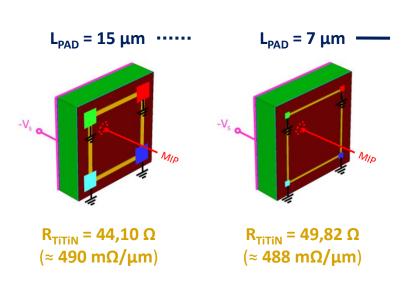
July 2020

# Active (TV) behavior

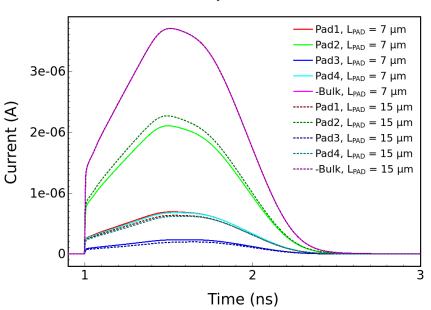
✓ 3D structure, 2x2 PADs, C w Strip (30 h 38 min, 8 lic.)

@ R<sub>s,n++</sub>  $\approx$  721  $\Omega_{sq}$ 

- o hit 3, 1 MIP
- $\circ$  V<sub>s</sub> = -110 V











# Active (TV) behavior

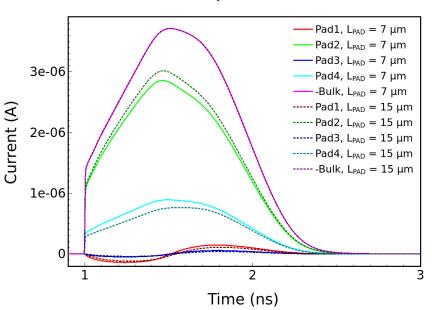
✓ 3D structure, 2x2 PADs, C w Strip (31 h 24 min, 8 lic.)

@ R<sub>s,n++</sub>  $\approx$  721  $\Omega_{sq}$ 

- o hit 8, 1 MIP
- $\circ$   $V_s = -110 V$

# $L_{PAD}$ = 15 μm ····· $L_{PAD}$ = 7 μm ····· $V_s$ $V_s$

## **I-t,** not irr.





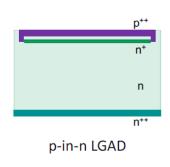


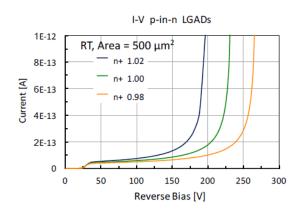
## Donor removal characterization

A production batch is needed to study the donor removal coefficient, c<sub>D</sub>

Donor removal has been studied for doping densities of  $10^{12} - 10^{14}$  atoms/cm<sup>3</sup> [M.Moll et al.] We need to study donor removal in a range  $10^{16} - 10^{18}$  atoms/cm<sup>3</sup>

NB: Oxygen has for donor removal a very similar effect of Carbon to acceptor removal





Simulation of the p-in-n LGAD parameters is in progress

→ The main goal of the p-in-n LGAD production is to study the c<sub>D</sub> evolution and its interplay with Oxygen co-implantation





## Next steps for DC-RSD

- ✓ **Identify the combinations of parameters** to reach the best performance.
  - ✓ Sheet resistance of the n<sup>++</sup> layer
  - ✓ Sheet resistance of the resistors between read-out electrodes
  - ✓ Pitch, pad size and its geometry
- ✓ The "New Univ. of Perugia TCAD model", which accounts for the bulk and surface radiation damage effects on silicon detectors, will be implemented to predict the RSDs electrical behavior after irradiation
- ✓ Manufacturing of the first DC-RSD production
- ✓ Validate and fine-tune the modeling used in the DC-RSD simulation, based on DC-RSD run 1.





# Reconstruction (2/2)

✓ The position is reconstructed using the CHARGE imbalance

$$x_i = \frac{Q_{top\,right} + Q_{bottom\,right} - Q_{top\,left} - Q_{bottom\,left}}{Q_{tot}}$$

$$z_i = \frac{Q_{top\,right} + Q_{top\,left} - Q_{bottom\,left} - Q_{bottom\,right}}{Q_{tot}}$$

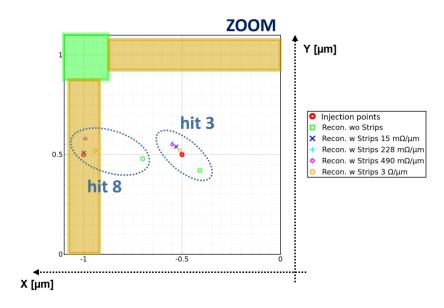
$$Pad \, Length = 15 \, \mu m$$

$$Pitch = 105 \, \mu m$$

$$@ \, V_{Back} = -110 \, V$$

$$1 \, MIP$$

$$R_{s,n++} \approx 721 \, \Omega_{sq}$$



**Results** from *TCAD* simulations



